

**PROCESS
TECHNOLOGY**



PULSAR

High Purity Inline Chemical Heater

Innovative precise temperature control at point of use.

PULSAR Benefits & Specifications

- Small size enables mounting near point of dispense
- Precision temperature control at the point of use
- Increased yield due to enhanced chamber matching
- Enhanced yield due to optimized temperature gradient across the wafer surface
- Reduced cost of ownership since decreased recirculation loop temperature extends bath chemical lifetime
- Improves cycle times by reducing time to achieve process temperature
- Reduces chemistry consumption by eliminating dispense to drain during temperature ramp
- Compatible with solvents and acids, including HF
- Flexible mounting orientation: vertical or horizontal

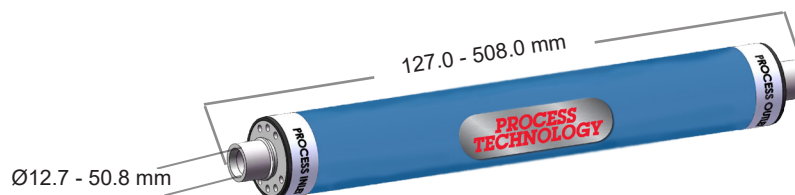
SPECIFICATIONS:

- Temperature Range: Up to 180°C
- Temperature Accuracy: $\leq \pm 0.1^\circ\text{C}$ depending on operating conditions
- Fluid Connections: 6 mm or 10 mm Pillar S300
- Pressure Range: 3 bar at 120°C
- Flow Rates: 0.1 lpm to 3 lpm
- Voltages: 120V - 480V, single phase.
- Standard Wattages: 50 to 2000 watts.
- Certifications: UL499 and SEMI S2.

SAFETY FEATURES (standard):

- Overtemperature sensor
- High limit thermal protector.

DIMENSIONS:



*Dimensions of the unit to change with custom configuration.

Patent Pending